## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

in re Patent Application of:		)
	Shinichiro Nohdo	Group Art Unit: 2877
Application No. 10/812,602		Confirmation No.: 3173
Filed:	March 30, 2004	)   Examiner: Rebecca Slomski   
For:	WAFER, EXPOSURE MASK, METHOD OF DETECTING MARK AND METHOD OF EXPOSURE	
Comm	STOP AMENDMENT hissioner for Patents tox 1450	

## RESPONSE TO APRIL 24, 2007 OFFICE ACTION

## Dear Sir:

Alexandria, VA 22313-1450

This Amendment is submitted in response to the Office Action mailed April 24, 2007.

Applicant respectfully requests reconsideration of the application in view of this amendment and remarks herein.